

REMARKS

Claims 1-11 and 39-49 are pending in the above-identified application. Claims 1-11 and 39-49 were rejected. With this Amendment, claim 1 was amended and claim 87-89 were added. Accordingly, claims 1-11 and 39-49 and 87-89 are at issue in the above-identified application. As Applicants forgot to enclose the Replacement Sheet and Terminal Disclaimer in the original Response, Applicants enclose both herewith.

Objection To Drawings

The Examiner objected to the drawings, indicating that Figures 1 and 2 should be designated by a legend such as --Prior Art--. Applicants respectfully traverse this objection.

Enclosed is a Replacement Sheet showing proposed changes thereto for which approval of the Examiner is requested. The proposed changes are to correct the drawing and do not constitute new matter. In particular, Figures 1 and 2 have been amended to designate the legend --Prior Art--. Accordingly, Applicants respectfully request withdrawal of this objection.

Double Patenting

Claim 1 of this application conflict with claim 1 of Application No. 11/103,809. Applicants enclose a Terminal Disclaimer to overcome this double patenting rejection. Withdrawal of this rejection is requested.

35 U.S.C. § 102 Anticipation Rejection of Claims

Claims 1-22 were rejected under 35 U.S.C. § 102(e) as being anticipated by *Yahiro et al.* (U.S. Patent No. 6,204,509). Applicants respectfully traverse this rejection. Withdrawal of this rejection is respectfully requested.

Claim 1 recites a mask-making member comprising a plurality of pattern formation

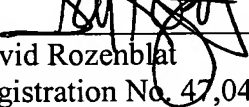
regions in which mask circuit patterns are to be formed and a supporting region in which any mask circuit pattern is not to be formed, wherein said supporting region has first alignment marks used at the time of exposure of a mask made from said mask-making member for forming said mask circuit patterns thereon, and second alignment marks used at the time of exposure of a substrate to be exposed for forming circuit patterns thereon, *wherein said first and second alignment marks are formed on a common surface of said supporting region*. None of the cited references teach or even disclose a supporting region which has first and second alignment marks, as recited in claim 1. For example, *Yahiro et al.* teaches a segmented reticle 5 comprising a uniformed-thickness film 7 that is transmissive to charged particles. The thin film 7 defines features of a pattern to be transferred from the reticle 5 to a sensitized substrate. Then, film 7 is divided into multiple "mask sub-fields" or 50 each comprising a membrane defining a respective portion of the pattern. (See *Yahiro et al.*, column 7, lines 29-36). Integral with the reticle thin film 7 is a support grid 52. (See *Yahiro et al.*, column 7, lines 48-49). In the embodiment of the reticle 5, shown in Figs. 1(a) and 1(b), an alignment mark 53 is formed preferably at each location where struts of the support grid 52 intersect each other. *Yahiro et al.* also teaches that in one embodiment, the reticle 5 is mounted to a reticle holder 30 using, for example, a static chuck 31. (See *Yahiro et al.*, column 13, lines 45-47). The reticle holder 30 is described as a separate structure, which is apart from the support grid 52. It appears that the reticle holder 30 has marks 301 formed upon it, as shown in Fig. 5. However, marks 301 are never discussed or taught in the specification for *Yahiro et al.* *Yahiro et al.* does teach or disclose that there are alignment marks 33 or fiducial marks, on the retical holder 30, which can be measured prior to mounting the reticle holder 30 in the pattern transfer apparatus. (See *Yahiro et al.*, column 13, lines 48-51). Alignment marks 33 are not shown in any of the Figures and therefore, it is difficult to ascertain

their exact location, however they are discussed being on the reticle holder 30, which is a separate structure from the support grid 52. *Yahiro et al.* never teaches or discloses forming two different types of alignment marks on a *common surface* of the same structure. Additionally, *Yahiro et al.* never teaches secondary alignment marks having a pattern formed from a plurality of *lines with spaces* between said lines. *Yahiro et al.* only teaches using alignment marks in the shape of a cross hair. Accordingly, Applicants respectfully request withdrawal of this rejection.

In view of the foregoing, Applicants submit that the application is in condition for allowance. Notice to that effect is requested.

Respectfully submitted,

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